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Kusaki et al.

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(54) **METHOD FOR PRODUCING SUBSTRATE
FOR MAKING MICROARRAY**

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C40B 40/04 (2006.01)

C40B 50/18 (2006.01)

(52) **U.S. Cl.**

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(2013.01); **C40B 50/18** (2013.01); **B01J**
2219/00527 (2013.01); **B01J 2219/00596**
(2013.01); **B01J 2219/00612** (2013.01); **B01J**
2219/00626 (2013.01); **B01J 2219/00637**
(2013.01); **B01J 2219/00659** (2013.01)

(58) **Field of Classification Search**

CPC ... C04B 40/04; C04B 50/18; G01N 33/54353
USPC 427/2.11, 2.12, 2.13, 409, 410; 435/7.1
See application file for complete search history.

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(57)

ABSTRACT

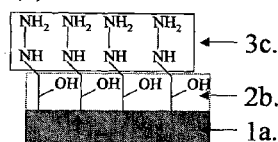
There is disclosed a method for producing a substrate for
making a microarray, the method comprising: at least, a step
of forming a monomolecular film having orientated oxysila-
nyl groups toward an outmost surface on the substrate; and a
step of forming a monomolecular film having orientated
amino groups toward an outmost surface on the substrate by
applying a solution containing a diamine compound to the
oxysilanyl groups. There can be provided a method for pro-
ducing a substrate for making a microarray in which density
and orientation of amino groups orientated toward an outmost
surface are controllable, and in addition, there is no delami-
nation of a monomolecular film formed on the substrate.

5 Claims, 1 Drawing Sheet

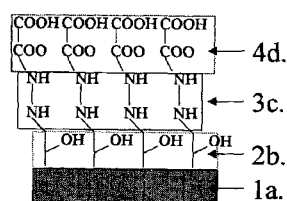
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